

About the Editors



Filipe Vaz (F. Vaz) graduated in Physics and Chemistry at the University of Minho, Portugal in 1992, where he obtained also his PhD degree in Physics in 2000. Since September 1992 he has been working at the Physics Department of University of Minho, involved in research areas related with thin films and their applications. Main research topics concern hard nanostructured thin films, with targeted applications varying from tools and machine parts, including polymers. From 2001 he is also developing new optical thin film systems, based on oxynitrides, oxycarbides, and their mixing. Recently, his research is focused on the physics and technology of magnetron sputtered thin films containing noble metal nanoparticles, namely gold and silver, revealing Surface Plasmon Resonance behaviour.



Nicolas Martin obtained a PhD in Physical Chemistry from the University of Franche-Comté in 1997 and an habilitation degree from the same University in

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2005. He was a researcher at the Ecole Polytechnique Fédérale de Lausanne from 1998 to 2000 in the Physics department. He was nominated as Assistant Professor at the National Engineering School ENSMM – “Ecole Nationale Supérieure de Mécanique et des Microtechniques in Besançon in 2000, and Full Professor in 2008. His research is focused on the physics and technology of metallic and ceramic thin films prepared by reactive sputtering. He is also interested in nanostructuring of coatings prepared by Glancing Angle Deposition (GLAD). He was the head of the Micro Nano Materials & Surfaces team (MINAMAS) in the Micro Nano Sciences & Systems (MN2S) research department of the FEMTO-ST Institute for 2008 and 2009. He is now one of the Deputy Directors of MN2S research department.



Martin Fenker studied Physics in Ulm and Heidelberg (Germany). He obtained a PhD in Physics from the University of Heidelberg in 1998. He was a researcher at the DaimlerChrysler AG Research Institute (ULM) from 1994 to 1999, studying the deposition of diamond coatings by using CVD methods. Since 1999, he is employed at the research institute for precious metals and metals chemistry (FEM) in Schwäbisch Gmünd (Germany), heading the department Physical Surface Technology. In 2004, this department merged with the Materials Physics department. He was appointed as head of this new department and its name changed to Plasma Surface Technology and Materials Physics (POT-MPh). His research is focused on thin film deposition by PVD and PACVD and coatings characterisation. He is interested in understanding the correlation between plasma process and thin film growth. Basic investigations are performed in High Power Impulse Magnetron Sputtering (HiPIMS) and PACVD with a Plasma Beam

Source (PBS). Beneath coating deposition of nitrides, carbides/DLC, oxides and oxynitrides *etc.*, surface modifications like plasma nitriding and combined processes (duplex) are explored.